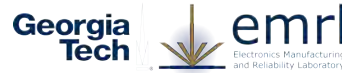


Development of Barrier Films for Packaging Flexible Electronics



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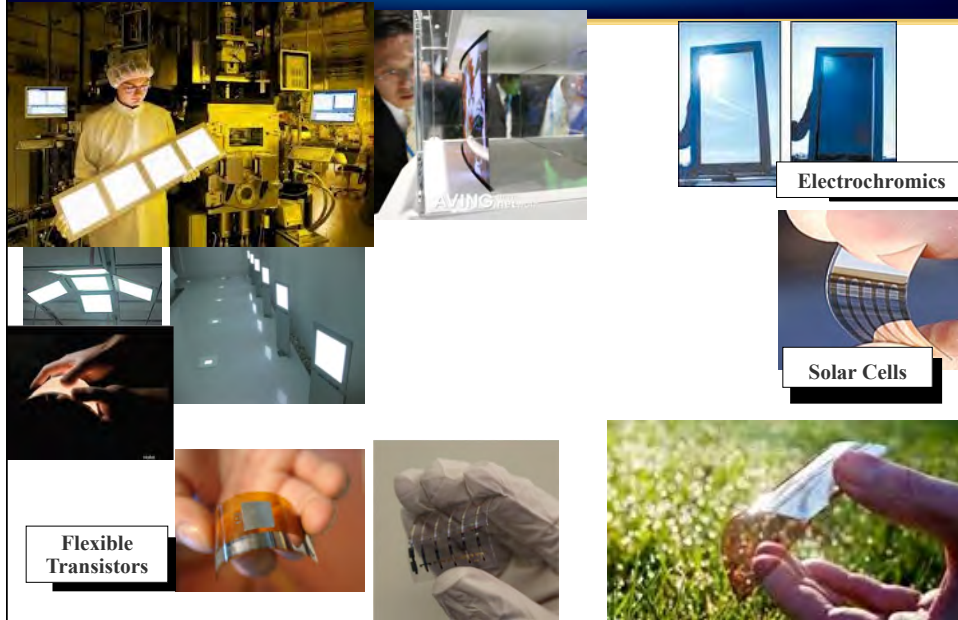
FACULTY/ Research Groups

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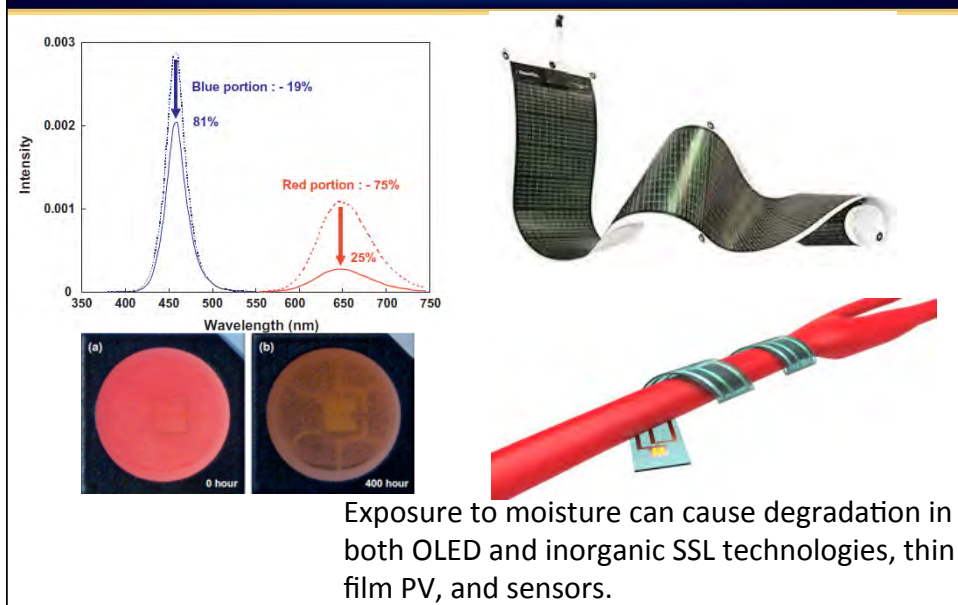
Sponsors

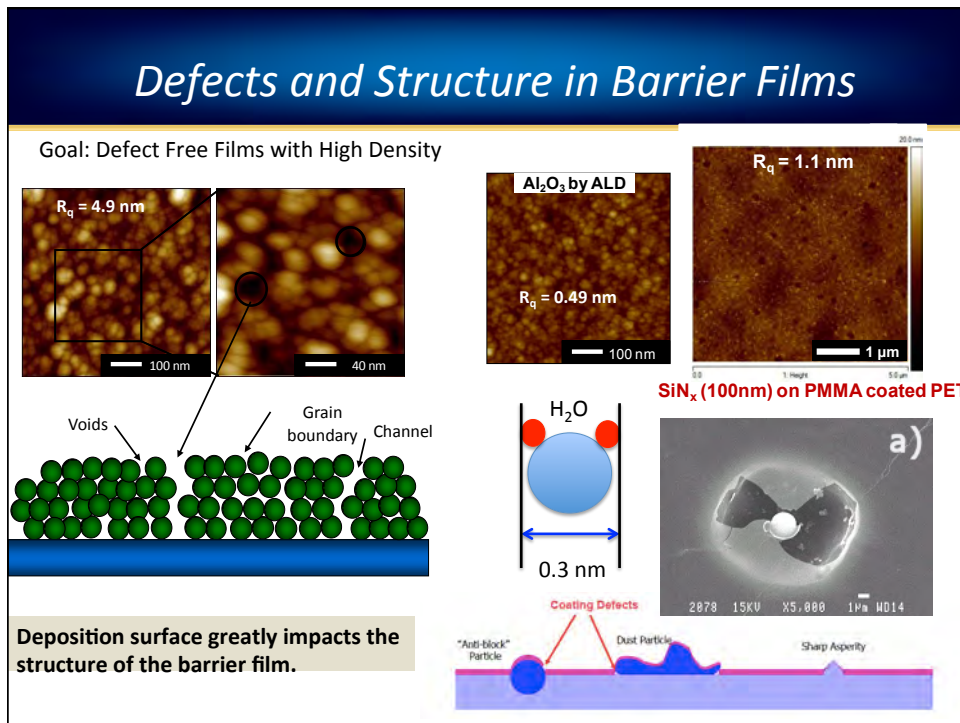
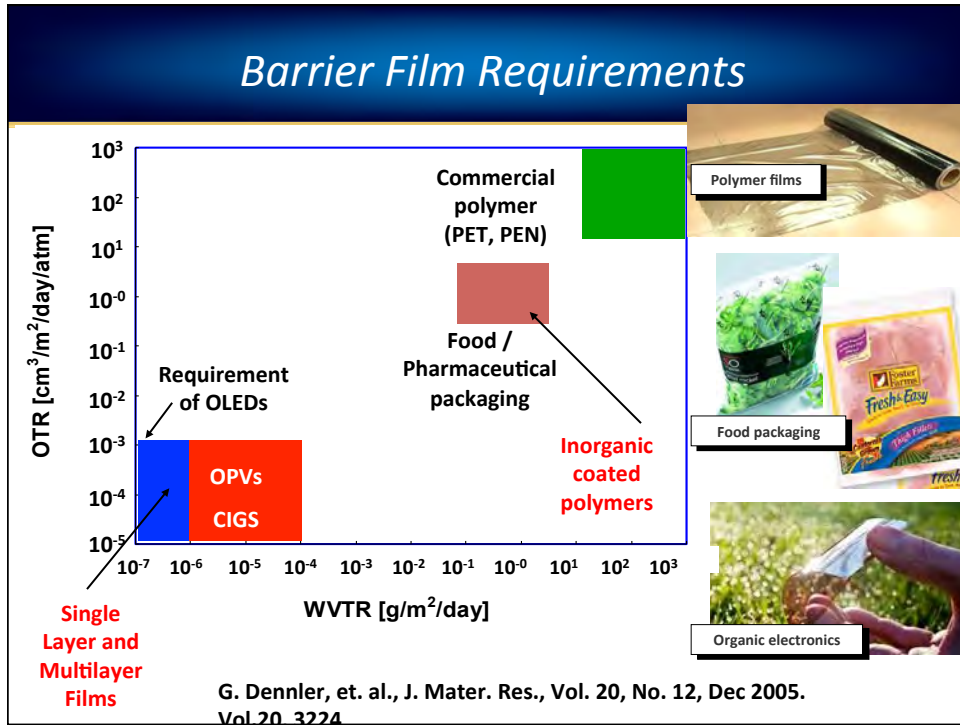
NSF, DOE Bay Area Photovoltaics Consortium, Applied Materials, SRC

Applications of Barrier Layers: Organic Electronics



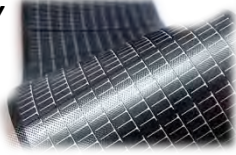
Challenges for Other Devices





ALD-based Hybrid Barriers

Low-cost, flexible encapsulation for thin-film PV

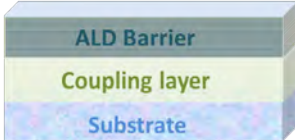


Atomic Layer Deposition (ALD):

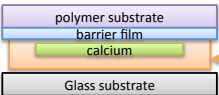
- Ultra-thin (<50 nm) conformal and flexible ceramic barriers
- WVTR < 10⁻⁵ g/m²-day
- Spatial ALD: high throughput, cost efficient to address manufacturing

ALD-based hybrid barriers:

- **Coupling layer: Mitigate Surface Defects and Control ALD Nucleation**
- **Materials: Range of metal oxides**
- **Create monolithic or nanolaminate films of stable ALD layers with Al₂O₃ at 100 °C.**



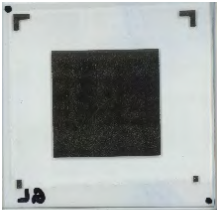

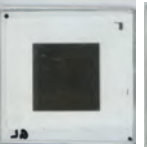
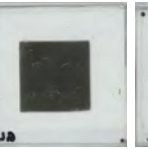
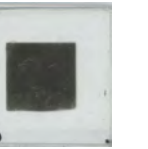
Permeation Analysis and Defect Detection

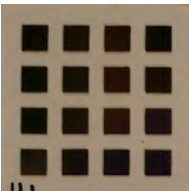
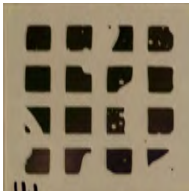


Laminated Barrier

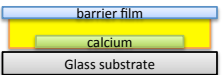
Transparent adhesive tape

Test in an environmental chamber at 85°C/85%RH

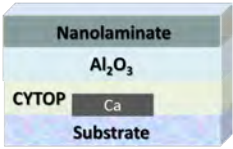
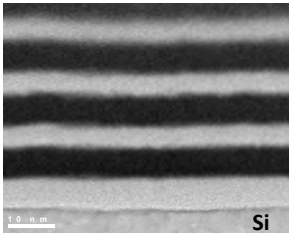



Direct Deposition



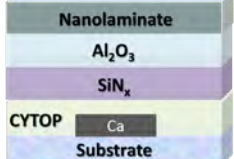
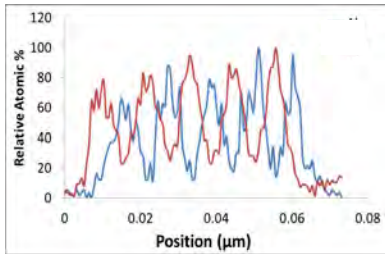
Barrier Layer Evolution

Sample A: Nanolaminate Structure

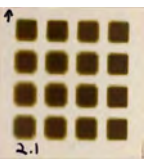
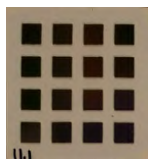
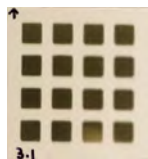
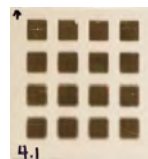
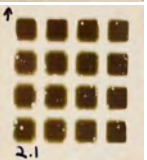

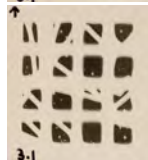

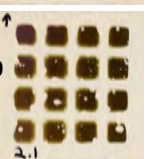
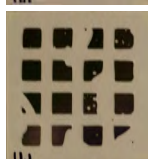
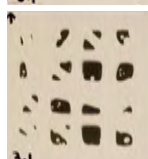

Nanolaminate Structure

Sample B: Nanolaminate Structure

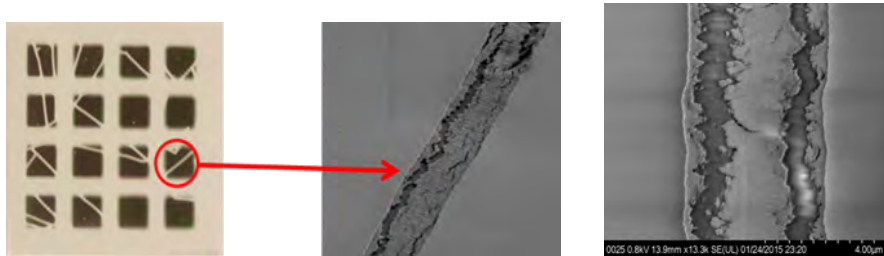
**Sharp interfaces in nanolaminate
No change in chemical structure after damp heat exposure for two weeks.**

Sample A @ 50°C/85% RH for 10 days

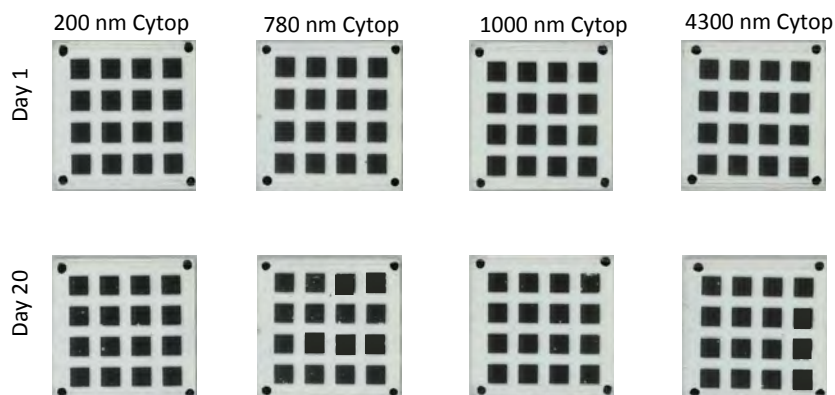
	200 nm Cytop	780 nm Cytop	1000 nm Cytop	4300 nm Cytop
Day 0				
Day 3				
Day 10				

Cracks in Barrier Films

- 1) Cracks developed with increasing thickness of Cytop opened large areas in the barrier film for water permeation
- 2) Local degradation rate from cracks was much more than that due to cracks

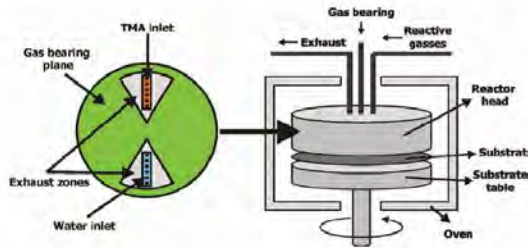


Sample B @50C/85% RH

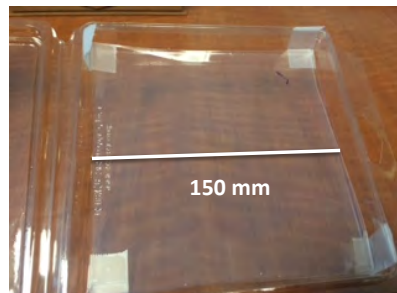


Spatial ALD of Barrier Films

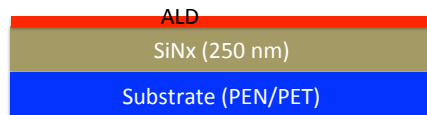
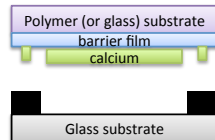
Collaborate with TNO/Holst Centre-
Findhoven, NL



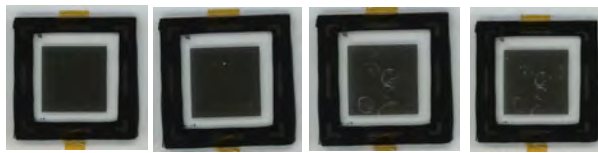
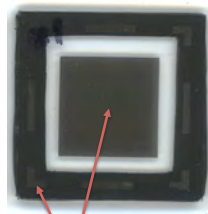
- Visit to TNO/Holst Center to deposit ALD layers on PECVD SiNx. Deposition of 10 nm ALD layers occurred within 10 minutes at 100°C using rotary reactor.
- Roll-to-Roll system is expected to take approximately 1 minute compared to 3-4 hours in viscous flow reactor.



Laminated Samples



Sample
in an environmental chamber at 85°C/85%RH

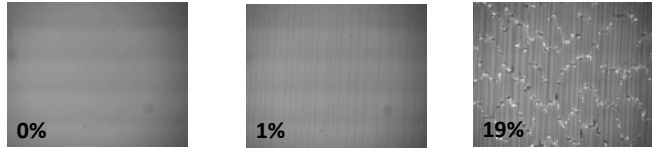


No noticeable change at least for ~200 hr at 85°C/85%RH

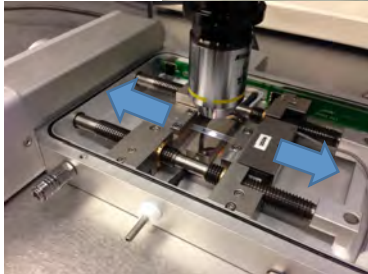
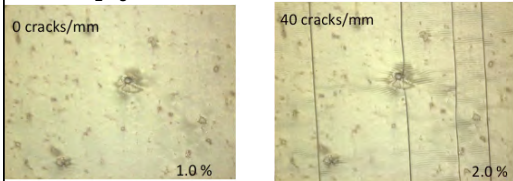
Mechanical Reliability: Strain To Failure

- Mechanical Testing Using Laser Scanning Confocal Microscopy
- Optical Microscopy

SiNx Coated PET

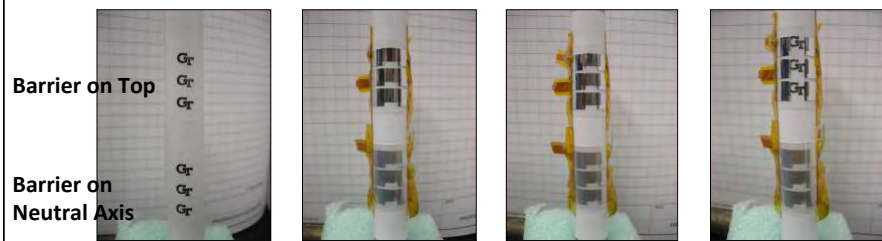


Al₂O₃ on PEIE Coated PET



Extending the Performance of Brittle Barriers

Designing the architecture such that you place the barrier on the neutral axis can reduce the strain on the film and improve performance under flexural deformation.



GT logo for eye inspection

After bending: R= 5mm

10 min

2 days

Solution deposited barriers and changes in material chemistry also provide routes to mechanically flexible barrier technologies.

N. Kim and S. Graham, Thin Solid Films, 2013.